

Notice of References CitedApplication/Control No.
09/863,150Applicant(s)/Patent Under
Reexamination
O'NEILL ET AL.Examiner
Timothy H. MeeksArt Unit
1762

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U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	A	US-6,147,009	11-2000	Grill et al.	438/780
	B	US-6,068,884	05-2000	Rose et al.	427/255.6
*	C	US-5,827,785	10-1998	Bhan et al.	438/784
*	D	US-6,410,463	06-2002	Matsuki, Nobuo	438/790
	E	US-			
	F	US-			
	G	US-			
	H	US-			
	I	US-			
	J	US-			
	K	US-			
	L	US-			
	M	US-			

FOREIGN PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N					
	O					
	P					
	Q					
	R					
	S					
	T					

NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
*	U	"Recent Progress in PECVD Low-k Dielectrics for Advanced Metallization Schemes", Lee et al. (no date available)
	V	
	W	
	X	

*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.